H2M: Characterization of a MAPS in a 65 nm CMOS Imaging Process

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HEI MHOLTZ





H2M (Hybrid-to-Monolithic)

Vertex detector requirements:

- ➤ Sensor thickness: ≤ 50 µm
- Spatial resolution: $\leq 3 \mu m$
- ► Time resolution: ~ ns
- R&D chip for a vertex detector at a future lepton colliders or as an upgrade to beam telescopes
- Ports a hybrid pixel detector architecture into a monolithic chip
- Digital-on-top design workflow
- Manufactured in a modified TPSCo 65 nm CMOS imaging process

- 35 μ m pixel pitch in 64x16 pixel matrix (sensitive area: 2.24 × 0.56 mm²). Thickness ~ 50 μ m (p-epi ~ 10 μ m)
- Analog and digital front-end per pixel

Data acquisition

- The chip can operate in **4 acquisition modes**:
 - Shutter signal enables acquisition
 - <u>Time over Threshold</u> (ToT, 8 bit)
 - Time of Arrival (ToA, 8 bit, 10 ns binning)
 - <u>Hit counting</u> (number of hits above threshold)
 - Shutter signal validates hit
 - <u>Triggered</u> (8 bit counter accounts for delay)
- Readout: 40 MHz clock, frame based, no zero suppression
- Integrated into the Caribou DAQ system <u>https://doi.org/10.22323/1.370.0100</u>

Threshold and ToT calibration

- **Threshold calibration** to find the relation between threshold-DAC and • electrons for comparison with simulations using k_{α} of Fe-55 and Ti
- **Test pulse calibration** to find the relation between ToT and signal • height per pixel
- Do Fe-55 measurement in ToT mode as Cross-check ٠ peak position agrees within 5%
- Double peak in amplitude spectrum: ۲ similar behavior observed in test chip; indicates ballistic deficit

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25000 20000 $\mu = 1683 \pm 2$ $\sigma = 109 \pm 2$ Entries 10000 5000 500 1000 1500 2000 2500 3000 calibrated ToT [e]

1000

1500

2000

Pixel [2,14]

Test-beam measurements at SPS and DESY II

- H6 beam line, 120 GeV charged pions.
- Timepix3 reference telescope.
 - Pointing resolution \sim 1.5 μ m
- Continuous DUT readout with 150 us (2.56 us) shutter duration for ToT (ToA) mode.

- Beamline 22, electron beam ~4.8 GeV.
- ALPIDE reference telescope.
 - Pointing resolution \sim 4 μ m
- External rigger closes shutter; open for O(1 ms)
 - Using Telepix2* with configurable ROI
 - Time resolution < 4 ns

Use similar corryvreckan analysis configuration

Efficiency and fake hit rate (triggered mode)

- No significant differences between bias voltages
- For a fake hit rate < 10 pixels/event, efficiency of 99.6% at a threshold of 144 e-(~5σ_{noise}) and -3.6 V

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- However, lower efficiency was measured than expected from simulations (using generic methods without proprietary information, and simulating the deep p-wells as flat profiles/nothing within the deep pwells <u>https://arxiv.org/abs/2408.00027</u>)

Non-uniformity in-pixel response

 \star Collection electrode

Non-uniformity in-pixel response

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• Related to the size and location of the n-wells of the analog circuitry.

Non-uniformity in-pixel response – Mitigation

\star Collection electrode

High ikrum

Low ikrum

- -

- Additionally, effects of fast front-end and large pixel size
- Qualitatively confirmed by simulations with real profiles

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Time

Non-uniformity in-pixel response – Simulation

- Simulation procedure:
 - Electric fields: TCAD (Sentaurus) simulation with realistic doping profiles
 - Transients: Allpix-Squared Charge deposition and transport
 - Front-end response: Spectre
 - All of these steps are crucial
- Adding electronics noise and track
 resolution effects
- Good agreement
 - Only few percent difference
 - Similar shape (simulation tends to be more symmetric)

DESY. | H2M: MAPS in 65nm CIS | Finn King | 05-12-2024

Time resolution (ToA)

- Arrival time depends on track impact position→timing limited by non-uniformity of charge collection
- Better timing resolution for -3.6 V than -1.2 V due to more uniform charge-collection time across the pixel
- No possibility of time-walk correction since charge information is not available simultaneously

Cluster size and spatial resolution (ToT)

Spatial resolution in X (same in Y) $\sqrt{(10.8^2 - 3.8^2)} = 10.1 \,\mu\text{m} (\sim 35/\sqrt{12} \,\mu\text{m})$ and cluster size ~ 1

- Dominated by the large pitch of 35 μ m, even at low threshold
- Asymmetric residuals in the row direction due to the low-efficiency part
- Analysis of rotation data ongoing (grazing-angle study) \rightarrow extract active thickness

Thin samples (ToT mode)

- Single-die backside thinning of H2M samples, performed by <u>OPTIM WS</u>
 - 30, 25, 24, 21 µm physical thickness

- No performance degradation from thinning
 - Efficiency >99% for ~200 e- threshold
- Studying thinning down to below 20 microns
 - Includes ~5 μ m circuitry + ~10 μ m epitaxial layer

Summary

- Fully functional monolithic sensor in a 65 nm CIS designed in digital-on-top workflow
- Calibration and characterization of performance with laboratory and test beam measurements
 - Efficiency 99.6% at a threshold of 144 e- (~5 σ_{noise})
 - Spatial resolution 10.1 µm (expected from pitch)
 - Thinning down to 21 μm without performance loss
- Impact of n-wells on charge-collection
 - Non-uniform in-pixel response affects timing
 - And efficiency for high thresholds and ikrum
 - Reproduced in simulations

Outlook

- Analysis of rotation data (grazing-angle study)
- Investigating thinning the chips to a total thickness < 20 μm
- PIXEL proceedings [Sara Ruiz Daza] and [Corentin Lemoine]

"The measurements leading to these results have been performed at the Test Beam Facility at DESY Hamburg (Germany), a member of the Helmholtz Association (HGF)".

Threshold equalization and single-pixel noise

- Equalization of the hit detection threshold:
 - 1) Threshold scan in counting mode for the 16 trimming values
 - 2) Determine the baseline for each pixel for each trimming value
 - 3) For each pixel, the trimming DAC is adjusted to the one that makes the closest to a fixed trimming target.
- Single pixel-noise obtained from width of threshold turn-on curves.

Triggered mode

Shutter (strobe signal) open for 500 ns vs O(ms) in ToT/ToA

- \rightarrow <u>Efficiency</u> compatible with the other acquisition modes
- → <u>Fake rate</u> reduced by a factor of about 100
- → <u>Minimum threshold achievable</u> ~ 144 electrons

- Strobe window duration accounts for time walk (~ 100 ns).
- **Preset** value accounts for the trigger latency.

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Measurements with a laser setup

- Backside incidence with an infrared pulsed laser. Light intensity tuned to correspond to the ToT MPV signal of 1 MIP.
- Confirmation of the **in-pixel efficiency pattern** observed in the test beam measurements and its orientation.
- **Pixel-to-pixel differences** attributed to different returns to baseline due to differences in the circuit's Krummenacher current and feedback capacitance.

ToT calibration

1.Amplitude vs dac_vtpulse

+ **2.ToT vs dac_vtpulse**

